

JAN 11 2007

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant:	Hong-Jyh Li et al.	Examiner:	Quoc Dinh Hoang
Serial No.:	10/799,910	Group Art Unit:	2818
Filed:	March 12, 2004	Docket No.:	2004P50029US/I331.135.101
Title:	ION IMPLANTATION OF HIGH-K MATERIALS IN SEMICONDUCTOR DEVICES		

AMENDMENT AND RESPONSE

Mail Stop Amendment
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Dear Sir:

This Amendment and Response is in reply to the Non-Final Office Action mailed August 11, 2006. Please amend the above-identified patent application as follows: